

# Sawatec & Präzitherm Coater Line for MISC polymers: User Manual

Version of 2024-11-25

## 1. Introduction

This user manual explains how to operate the Sawatec LSM-250 & Präzitherm coater line for the coating and drying/curing of misc. polymer thin films. In this line, a combination of two hotplates and spin coater offers maximum flexibility for various type of deposition process.

**NOTE: MATERIALS TO BE COATED IN THIS LINE SHOULD BE REVIEWED BY THE CMi COMMITTEE. COATING OF STANDARD PHOTORESIT ARE NOT ALLOWED IN THIS COATER!**

List of compatible material and associated Standard Operating Procedure (SOP) are available here:

<https://cmiaccess.epfl.ch/restricted/indexWP.php>

Standard photoresists are not included in this list and must be deposited in dedicated coaters for photoresists.

## 2. Login

- Login on the “Z13 Sawatec Coater for MISC polymers” with CAE on zone 13 accounting computer.

## 3. Präzitherm Hotplate Settings

- Two hotplates are available for baking/curing of the films. One is equipped with a cover so that wafers can be baked under N2 flow/atmosphere.
- Make sure the Präzitherm hotplate controllers are turned on. If not, turn them on.



- The Präzitherm hotplates can operate in two modes:
  - Fixed temperature mode = “Regler”
  - Ramped temperature mode = “Rampenreg.Programmer”
- **WARNING: Maximum hotplate temperature is 350°C.**
- Select the preferred operating mode using the appropriate switch.



### 1) “Regler” mode:

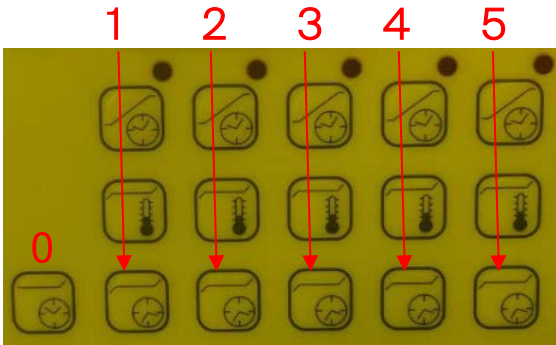
To adjust the temperature in this mode, maintain the “blue” button pressed and adjust the temperature set-point with the “up” and “down” arrows. Wait until the temperature is stable.



### 2) “Programmer” mode:

- In “Programmer” mode, users can edit three programs. Press “P1”, “P2” or “P3” to select these programs.

- Each program can hold a maximum of 5 steps (ramp time + wait time each).
- Edit each steps of program by maintaining the corresponding buttons and adjusting with the arrows. Temperature ramps will be linear up to the temperature set-point.



Ramp time [hr.min]



Temperature set-point [°C]



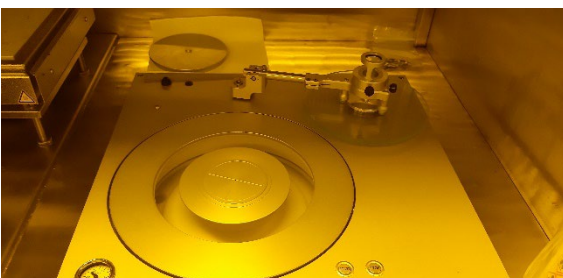
Wait time [hr.min]



- To start the selected temperature program, press "START".



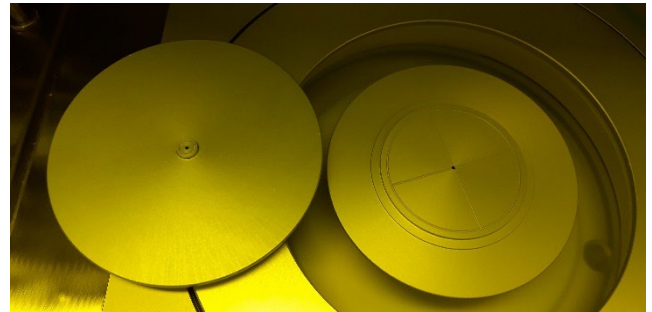
#### 4. Sawatec Coater Preparation



- Verify that the proper chuck is installed. Two chucks are available on the system: 1) Chuck for small chips, 2) 4inch wafer chuck.
- **CHUCK EXCHANGE:**
  - Make sure to wear a second pair of

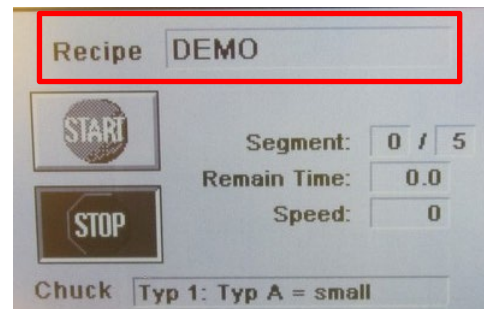
nitrile gloves during exchange of chucks.

- Remove the chuck by lifting it up.
- Make sure the three pins are present. If one is missing, it might have fallen into the vacuum hole. Contact the Staff if it is the case!
- Look at the pin position to insert the new chuck and press firmly for correct chuck leveling.



#### 5. Recipe selection and operation

- Recipe selection is done by pressing the following buttons:



- Select the process in the list. The recommended processes are :
  - STD\_XXXX (wafers and low viscosity PR)
  - HV\_XXXX (wafers and high viscosity PR)
  - CHIP\_XXXX (small chips)

**Warning: Recipes are edited by the CMi Staff. Do not edit them!!**

- Dispense the material to be spinned at the center of the wafer using the disposable pipettes or manually. 2-3 ml are sufficient for a 4inch wafer.

- Make sure that the cover glass is not obstructed by any objects and start the process.
- Press the “START” key to execute the coating process.



- Wait for process completion. The cover glass will move back to standby position.
- The wafer is then ready to be transferred to the hotplate.
- Make sure to check the temperature with the surface probes and adjust the setpoint if necessary.
- Measure the softbake duration with a timer
- Repeat for each wafer.